

09/927,102

PATENT

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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

U.S. Patent Application of
Michael Weber-Grabau, et al.

Application No.: 09/927,102

Filed: August 10, 2001

For: CRITICAL DIMENSION
METROLOGY SYSTEM
INTEGRATED INTO
SEMICONDUCTOR WAFER
PROCESS TOOL

Confirmation No.: 3815

Group Art Unit: 2877

Examiner: Richard A. Rosenberger

**RESPONSE TO OFFICE ACTION
MAILED NOVEMBER 10, 2005**

353 Sacramento St., Suite 2200
San Francisco, CA 94111
(415) 772-4900

M/S AMENDMENT
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States Postal Service as First Class Mail in an envelope, addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450 on April 4, 2006.

STALLMAN & POLLOCK LLP

Dated: 04/04/2006 By: Lana T. Brenner

Sir:

In response to the Office Action mailed November 10, 2005, please amend the above-identified application as follows:

Amendments to the Claims are reflected in the Listing of Claims that begins on page 2 of this paper.

Remarks begin on page 7 of this paper.

04/07/2006 SDENBOB1 00000038 09927102

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Atty Docket No.: TTI-31000